

# METHOD OF STABILIZING OXIDE ETCH AND CHAMBER PERFORMANCE USING SEASONING

## Abstract of the Disclosure

Undesirable reactions (such as formation of volatile compounds or complexes) are recognized to occur during production processes (such as etching with fluorine) at interior surfaces of a reactor chamber (such as a silicon-based reactor chamber). These undesirable reactions may be minimized and controlled by priming the chamber surface by incorporating seasoning atoms and/or molecules.

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